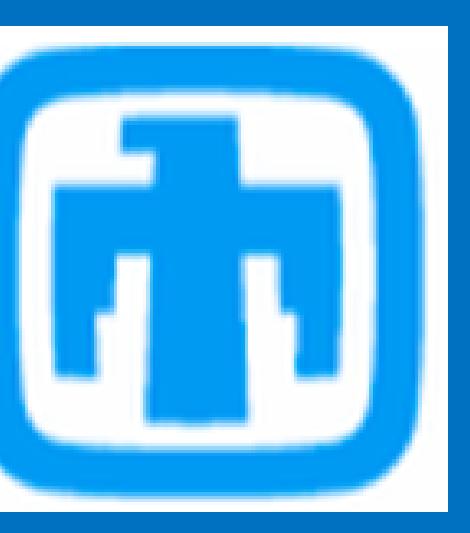




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SiGe-based Bilayers

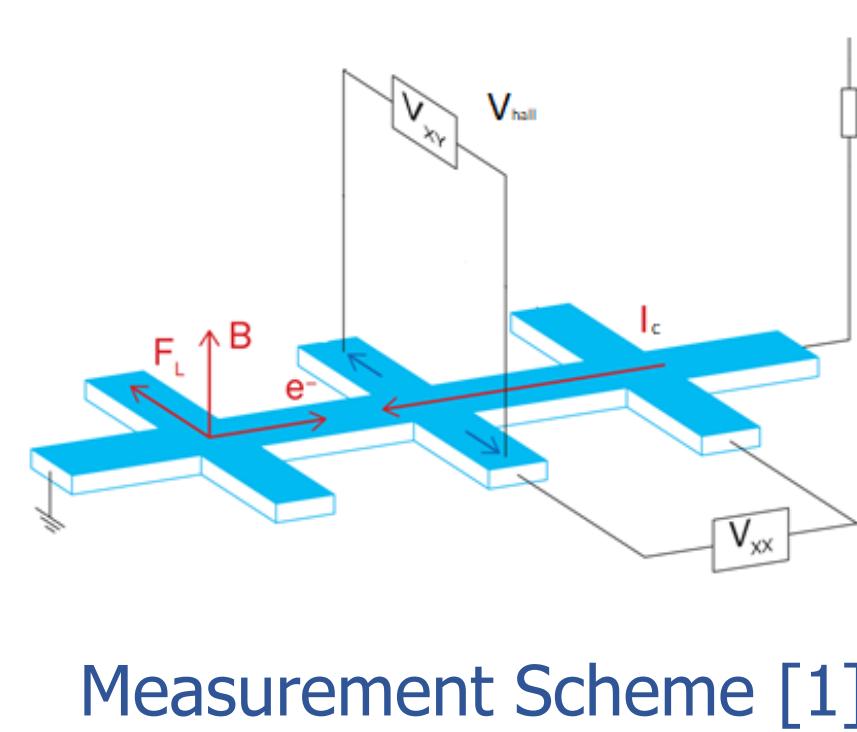
Undoped SiGe-based **quantum Hall bilayers** have been proposed as a platform for topological quantum computing^[3] by utilizing the **spontaneous interlayer coherence (SIC)** that arises as a signature of indirect **exciton condensation** and for **valley splitting** tuning for the realization of long-lived Si spin qubits.

Quantum Hall Effect

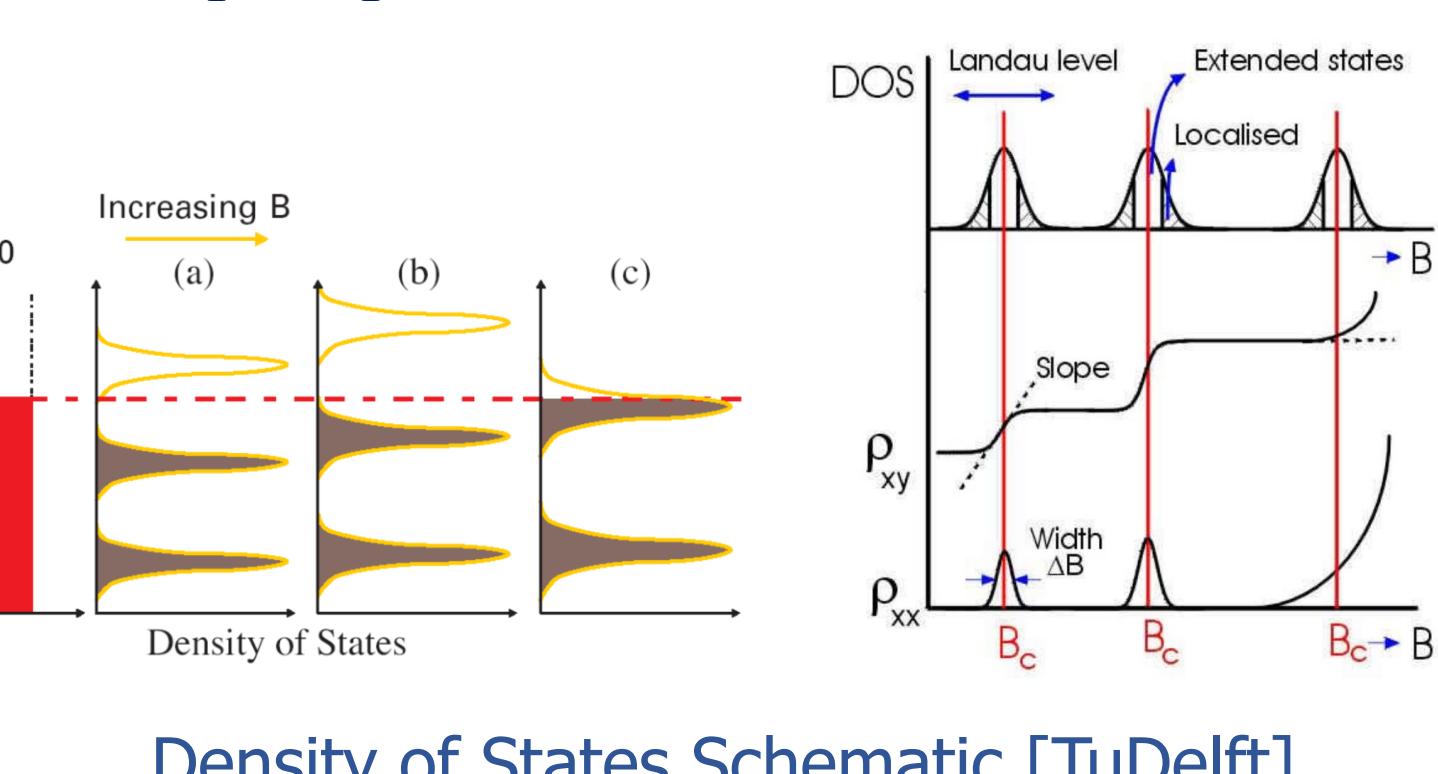
At low T and high B_{\perp} the Hall resistance, R_{xy} , exhibits steps that take on **quantized values** depending solely on **fundamental constants**, e and h:

$$R_H = \rho_{xy} = R_K/v = h/e^2v$$

$$[v_T = n_T/(eB/h)]$$



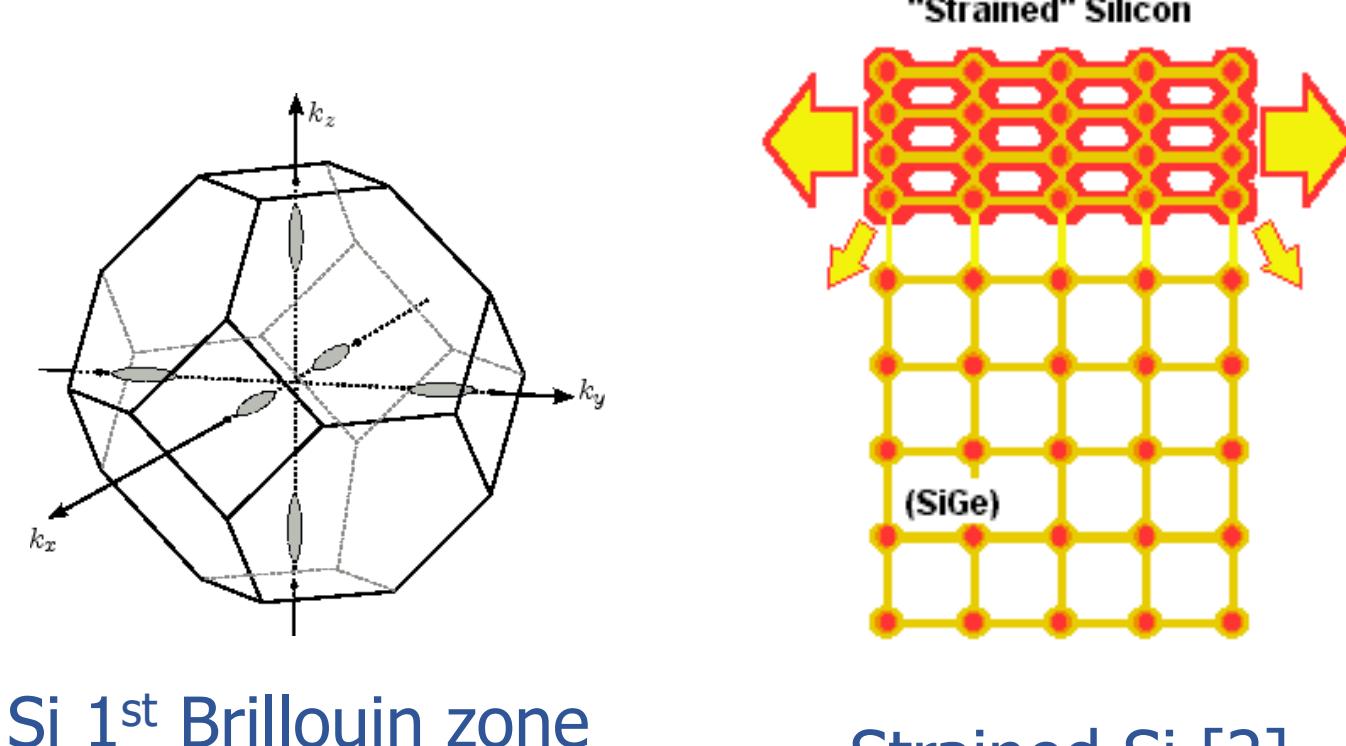
Measurement Scheme [1]



Density of States Schematic [TuDelft]

Valley Splitting

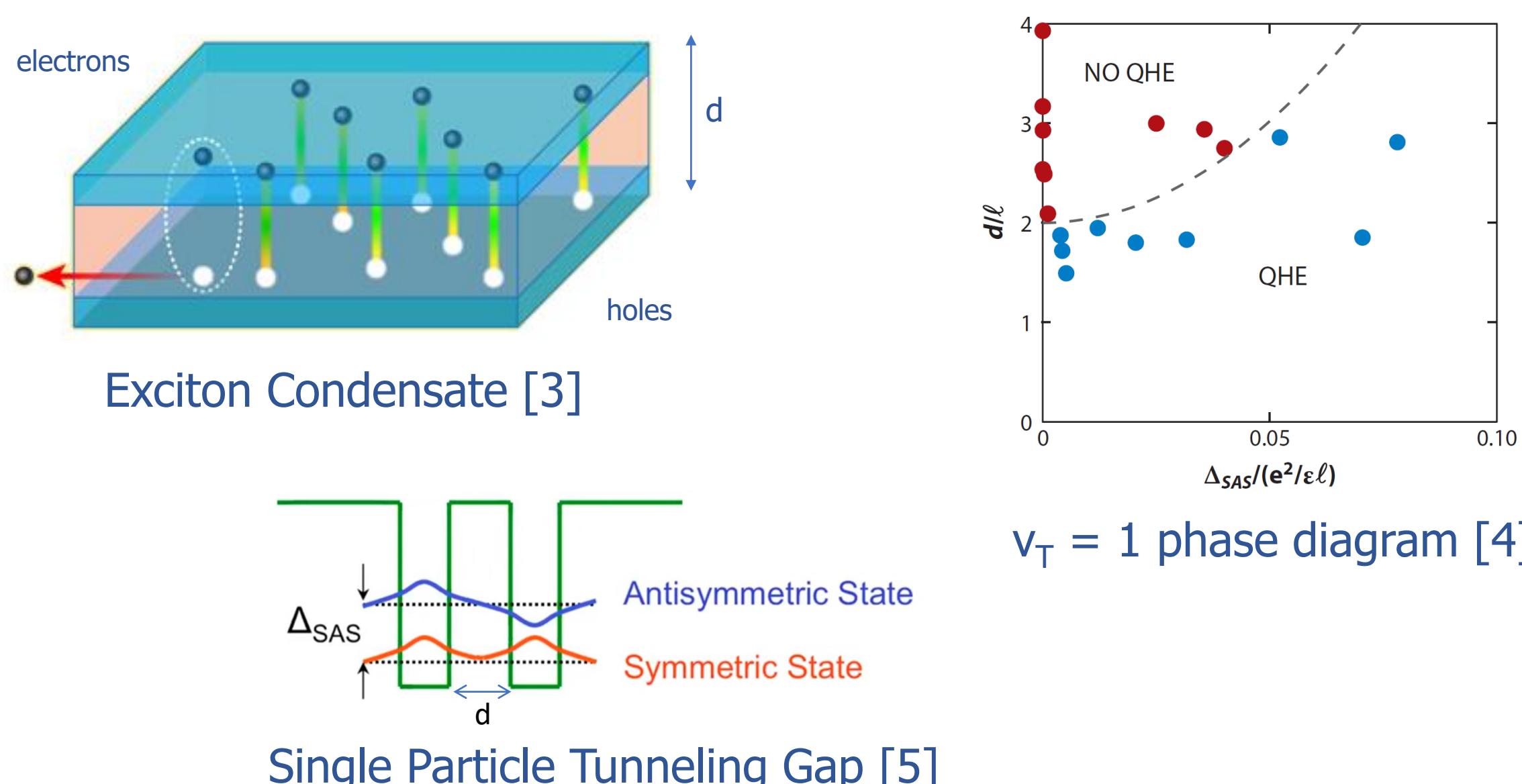
Through tensile strain and quantum confinement, the 6-fold valley degeneracy of bulk Si can be reduced to **2-fold**.



Strained Si [2]

SIC

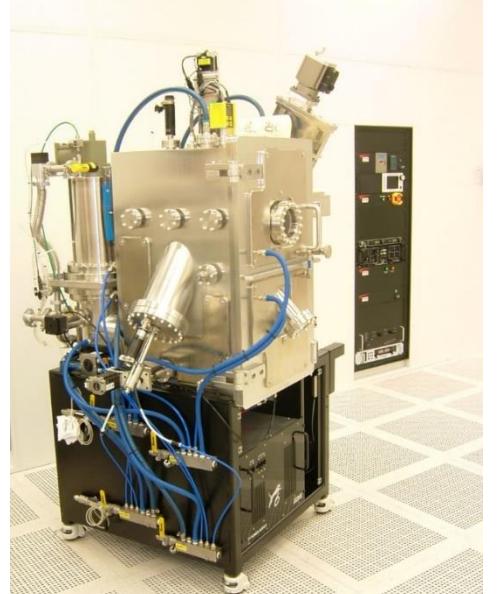
When 2 parallel 2DEGs are brought close together, a **coherent** many-body state of matter that occurs solely due to Coulomb interactions at the **limit of low interlayer tunneling**.



Nanofabrication is done at UF's NRF.

Left: E-beam evaporator, PVD
Right: Karl Suss MA6

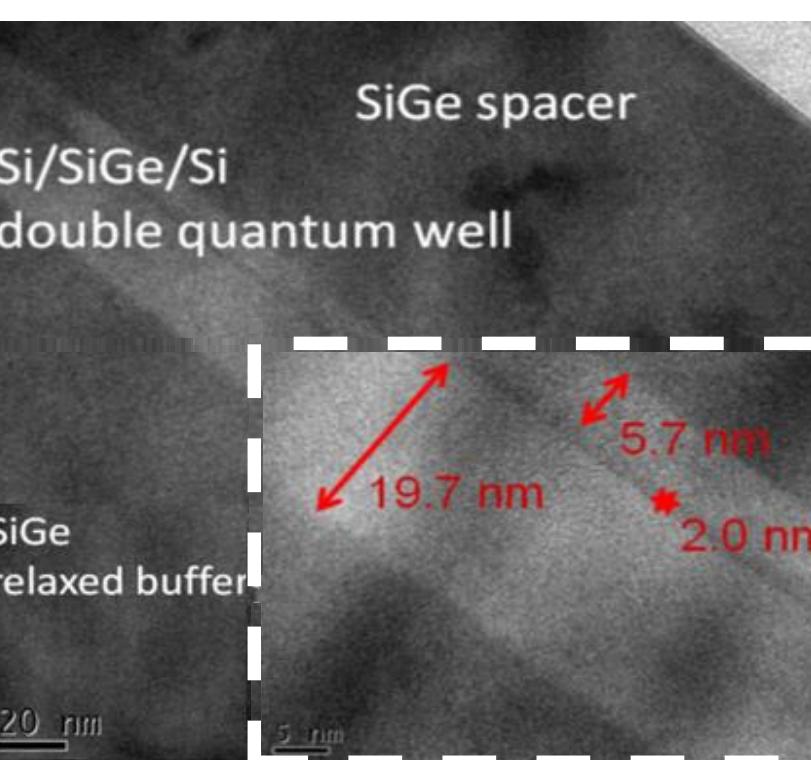
Infrastructure and Crew



New cryo-free Blue Fors system capable of reaching $T \sim 10$ mK & $B_z = 6$ T

SiGe Device Fabrication

A **dual-gated** bilayer Si/SiGe device, fabricated using standard photolithographic techniques, allows independent control of the density in both layers.



SiGe Bilayer [6]

Measurements

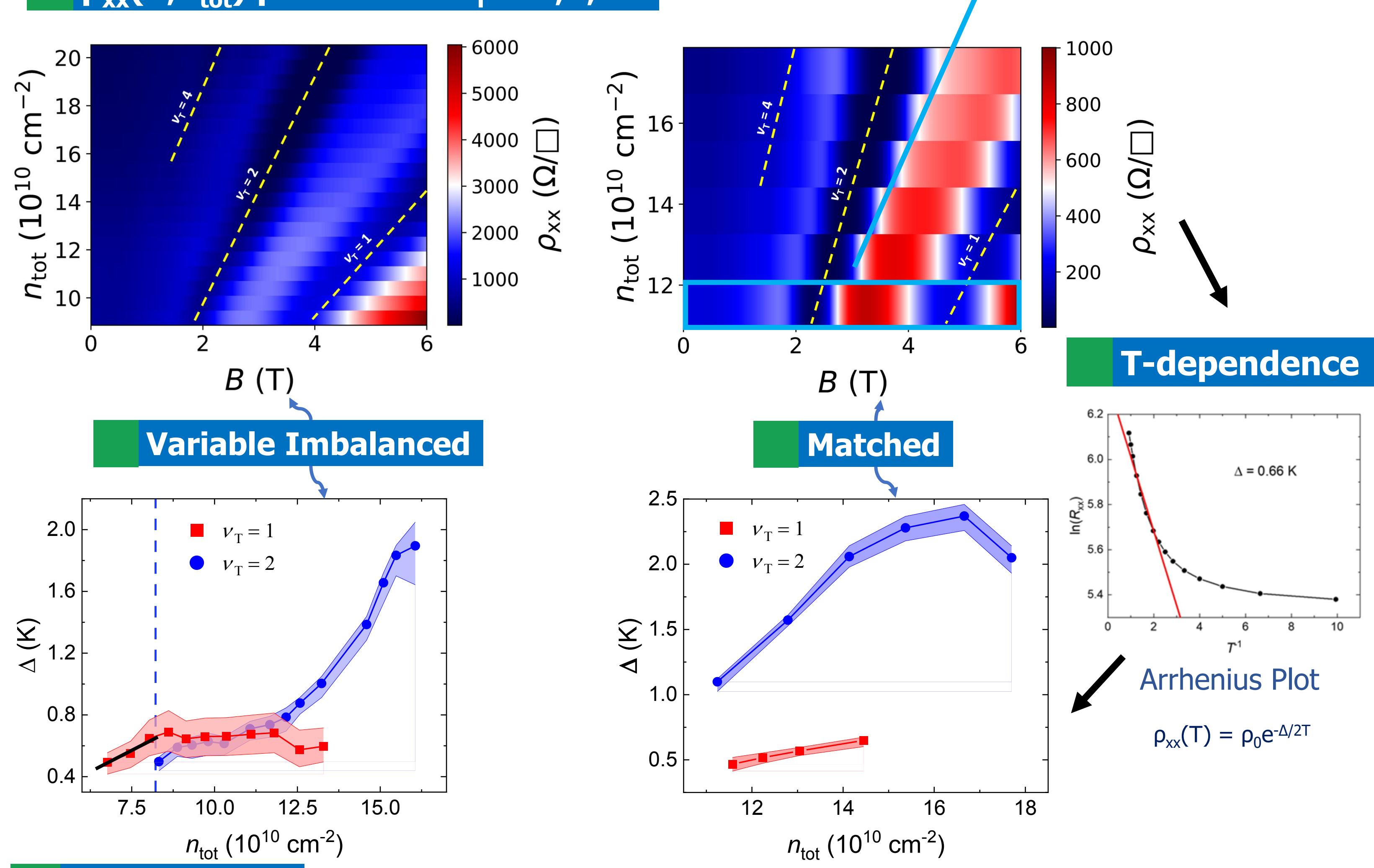
- Low-frequency (~9-50 Hz) lock-in amplifiers
- four-point geometry** w/ constant excitation current (~1-50 nA)

Key Results^[7]

$n_{\text{crossover}}$

Bilayer behavior is observed due to increased scattering.

$\rho_{xx}(B, n_{\text{tot}})$ plateaus at $v_T = 1, 2, 4$



Key Findings $\Delta_{1,2}(n_{\text{tot}})$ non-linear evolution for $v_T = 1, 2$

Single Layers: Disorder broadening, $\Gamma \approx 0.327$ K and linear coefficient, $c_B \approx 0.29$ K/T

Current crew: (top right to back left)

Rebika Makaju, Chris Cravey, Davis Rash, Harith Kassar, Dominique Laroche, Mert Daloglu, Suyang Cai, and Davis Chen



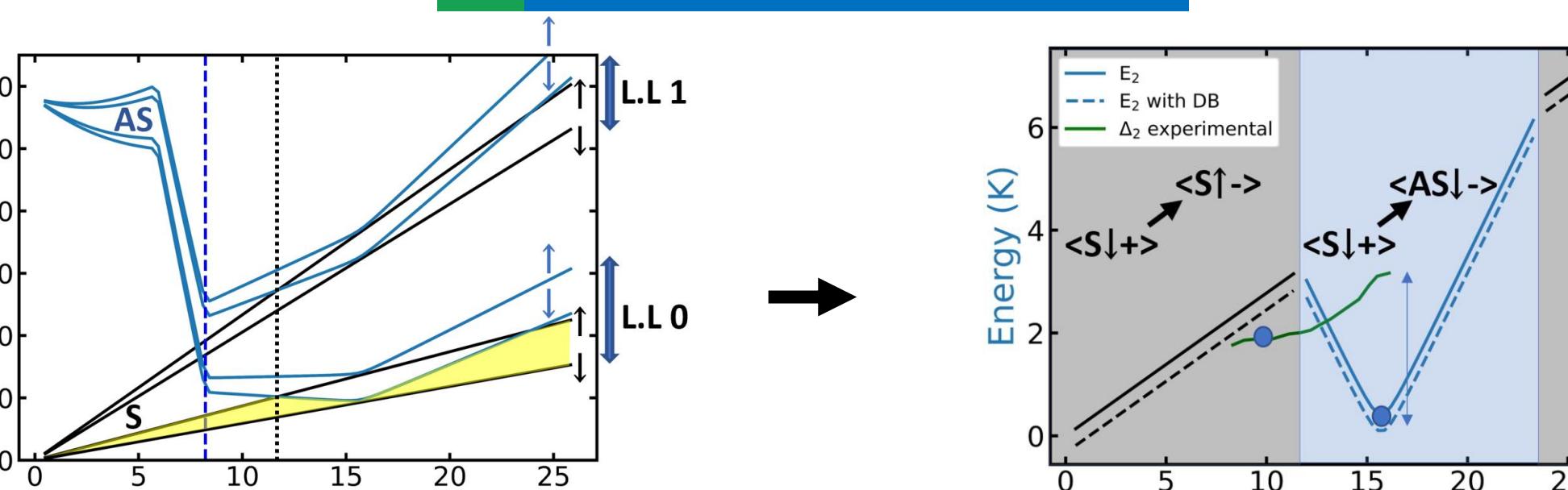
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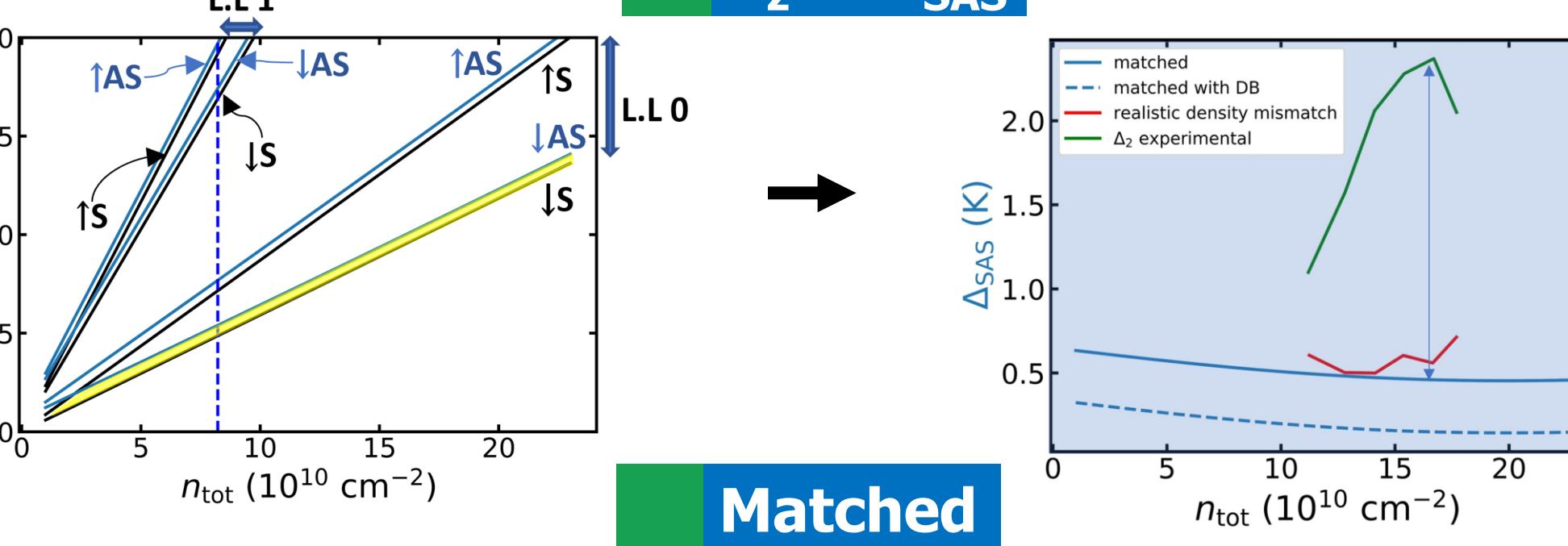
Analysis^[7]

Schrödinger-Poisson (SP) simulations were used to reproduce tunneling behavior through $n_{\text{crossover}}$ and the even energy splittings, E_{2n} . When considering the **degeneracies** of our system, we can attribute v_T to either interlayer effects or valley splitting.

Variable Imbalanced



E_z & Δ_{SAS}



Matched

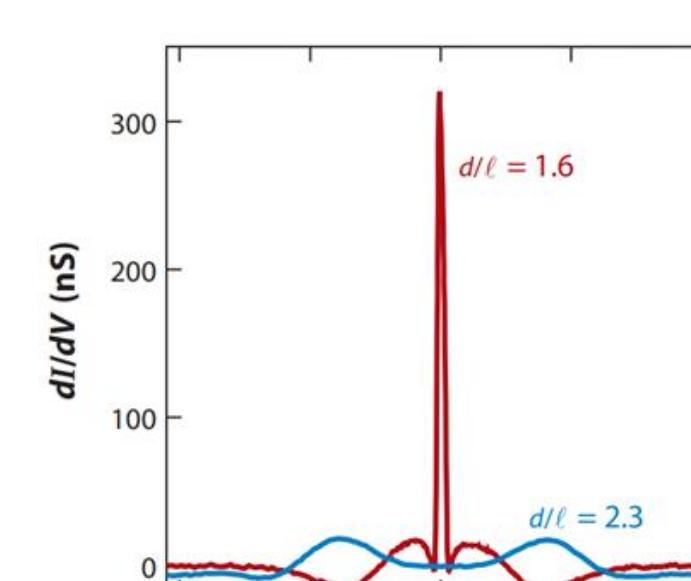
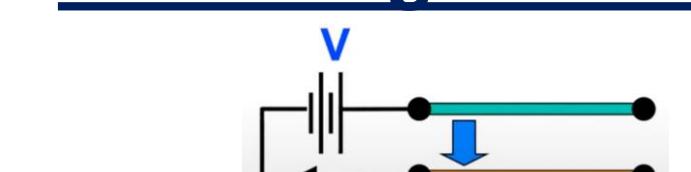
Future Work

Future Si/Ge devices will be fabricated in-house at UF's **Nanoscale Research Facility (NRF)** in hopes of realizing independent contacts to both layers or to Ge wells.

Independent Contacts

A scheme for independently contacting **both layers simultaneously** can unlock a host of new measurements:

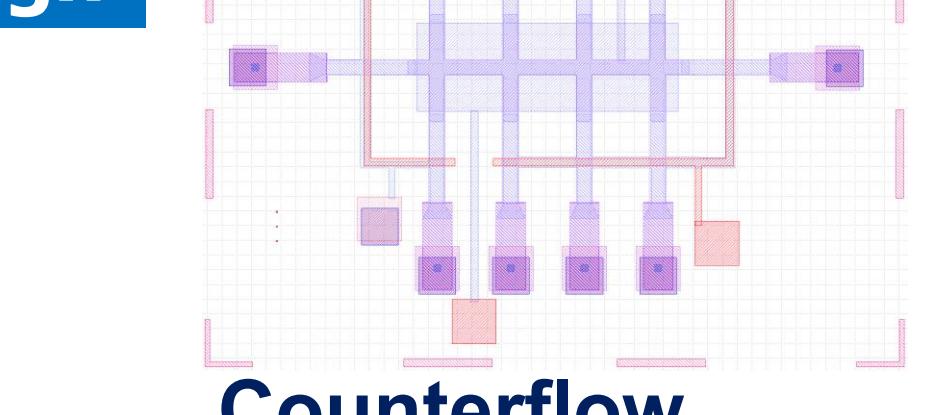
Tunneling Conductance



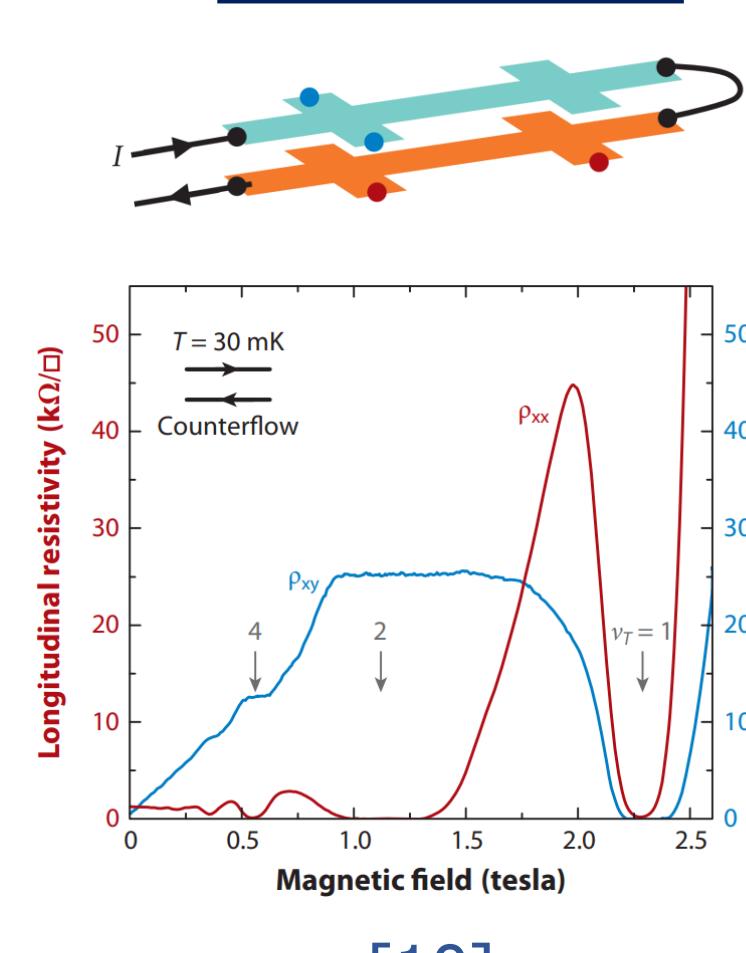
Arrhenius Plot

$$\rho_{xx}(T) = \rho_0 e^{\Delta/2T}$$

Mask Design



Coulomb Drag



[10]

Counterflow



[9]

Key Conclusions

- Signature of exciton condensation:** $v_T = 1$ and large excitation gaps, Δ .
- Large valley splitting at low B or spontaneous valley polarization.**

Outlook

Fabricating a SiGe bilayer with **independent contacts** to both layers will unlock a host of measurements to further study the signatures of SIC: **tunneling conductance**, **Coulomb drag**, and **counterflow** measurements.

Acknowledgement

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